**Limitations:**

The ZnO thin film deposition is a hard process, as it need to maintain a clean and dust-free environment, which is quite tough. The glass substrate must be cleaned perfectly and scratch free, which is quite impossible to observe in open eye. So, the whole process has uncertainty of success till the last of the process. Even after the deposition of the film of solution, it mandatory to prevent from the contact of the air, as the air molecules or dustup can distort the film. So, it is very hard to prepare and maintain a perfect thin film of ZnO. After the glass cleaning, the timing is also a factor. The times of coating and heating or drying process should be in a controlled way or the deposition won’t be uniform and perfect.